

VLSI Design

① VHDL Modelling

- i) Data flow modelling
- ii) Behavioural -11-
- iii) Structure -11-
- iv) Mixed -11-

In terms of engg.
we are interested
in the Mathematical
modelling.

② HALF ADDER

The library which we
generally use is (IEEE)

the package we use from
the library is
(std-logic_1164.all)

entity - define i/p & o/p

Keywords for structural
i) component
ii) signal
iii) port map

In structural modelling
we deal with comp.info
& their interconnection

library IEEE library

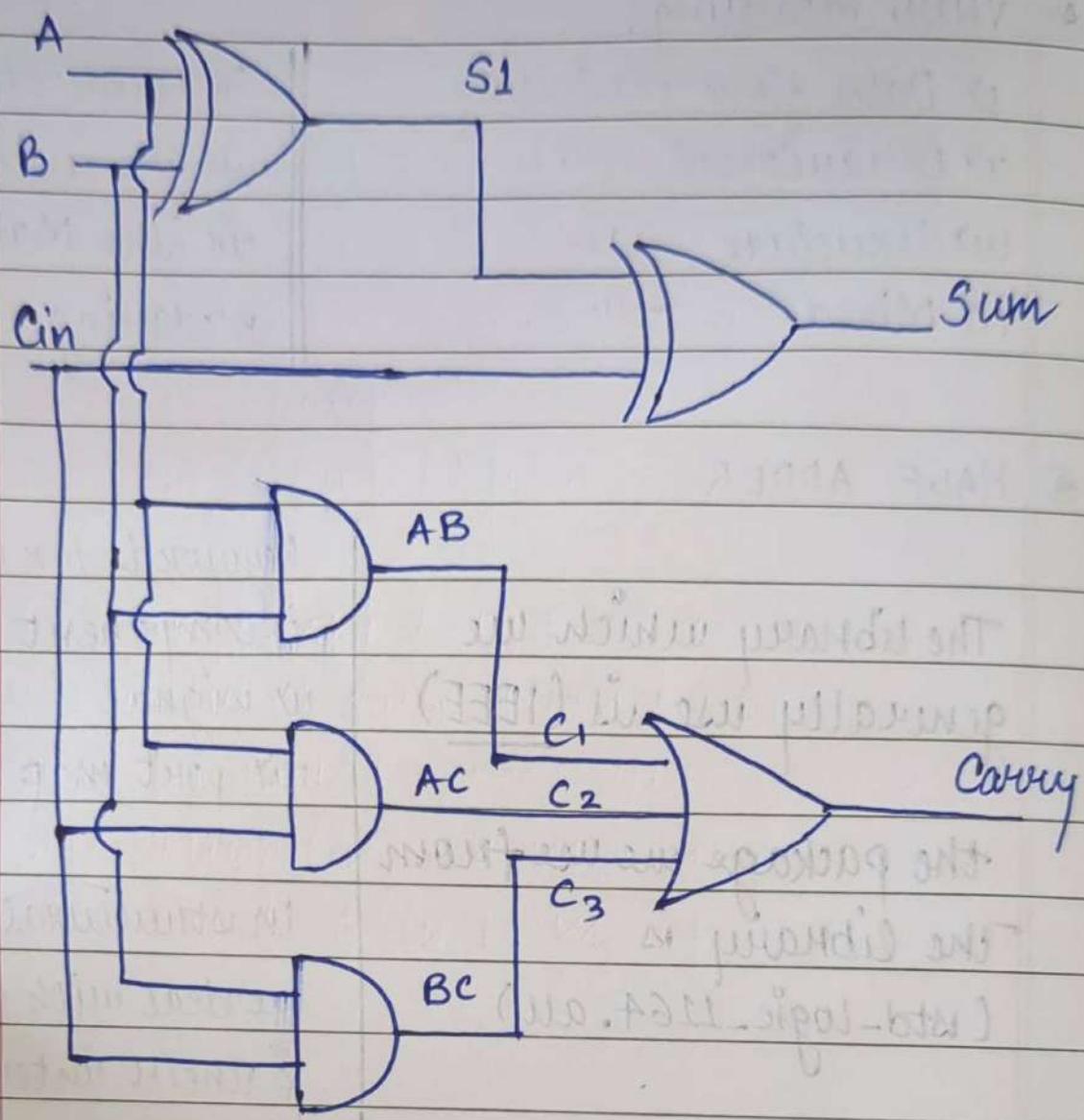
use std-logic_1164.all package

Entity

A, B, Cin : IN std-logic entity

Sum, Carry : OUT std-logic

Architecture



★ Structural Modelling

For structure modelling, we deal with components & their interconnection :

Component

component XOR21

$A, B = \text{in-std-logic}$

$C = \text{out-std-logic}$

Component AND21

A, B : in std-logic

C : out std-logic

we are not interested in defining all gates, we only define "Types of components"

Component OR21

A, B, C : in std-logic

D : out std-logic

(we use signal to define

Signal S1, C1, C2, C3 std-logic | intermediate signals)

U1: XOR21 portmap (A, B, S1)

U2: XOR21 portmap (S1, Cin, Sum)

U3: AND21 portmap (A, B, C1)

U4: AND21 portmap (A, Cin, C2)

U5: AND21 portmap (B, Cin, C3)

U6: OR21 portmap (C1, C2, C3, Carry)

before component is the
block of code from
library IEEE

to

entity [last page will]

here we have defined
the I/O points
and linked them
with intermediary
signals

★ VLSI design style

100%
custom

- 1) Full custom design (each & every transistors are bed down by designers)
- 2) Semi custom design
- 3) Standard cell based design
 - ↳ GATE array
 - ↳ FPGA | CPLD | PLD's

0%
↓

In Full custom design, we are concerned about W/L ratio of each transistor. Even the type of metal layer/wire which are interconnecting them. They start from scratch. They are best in terms of area, speed, power.

In Semi custom design most of the components are used which are prebuilt (library) & for the rest of components, we can design on our own.

On the basis of their customisation, we can broadly classify them as Fully, semi but for the point of understanding we can also add PLD based. i.e Full, semi & PLD.

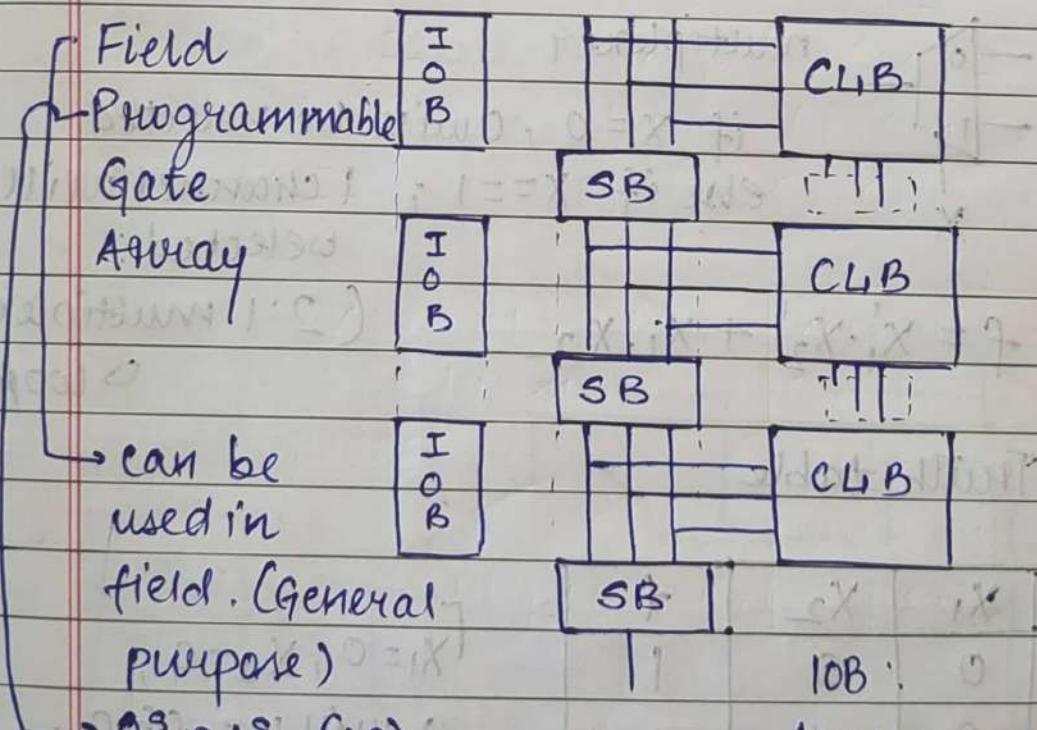
Time to market:- best FPGA > semi > Full
lowest fastest

[ASIC : application specific IC]

Parameters:	Full	Semi	FPGA
Time to market	max	< >	min
cost	max (if fabricating single)	< >	min
performance	best (ASIC) ☺	in b/w.	not feasible
area	min	in b/w	max

FPGA

28-09-2022



→ can be used in field. (General purpose)

→ OS & IS. (IC)

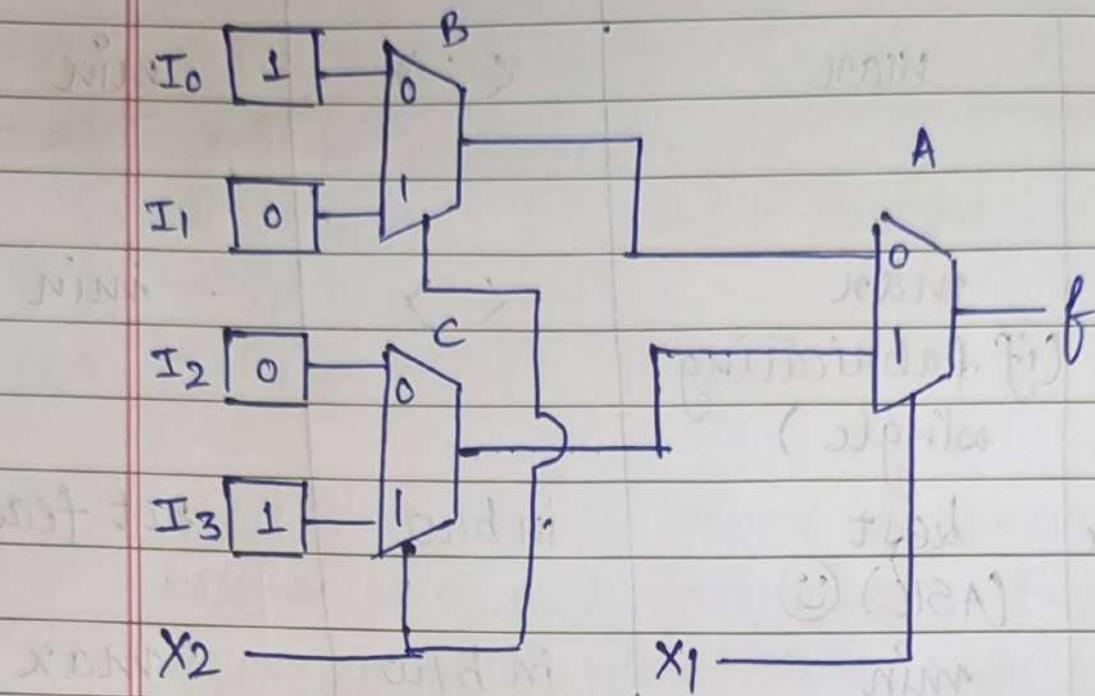
Interconnecting wires can be programmed

- Interconnect wires

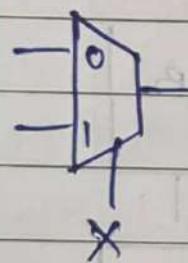
- Configurable logic blocks

- switch box

★ CLB: Configurable logic block



LUT: look up table



multiplexer

if $x = 0$, 0 will be selected

else if $x = 1$; 1 channel will be selected.

$$f = x_1' \cdot x_2' + x_1 \cdot x_2$$

(2:1 multiplexer)

↳ lookup

Truth table

x_1	x_2	f
0	0	1
0	1	0
1	0	0
1	1	1

$x_1 = 0, x_2 = 0;$

A will use 0 & 0,

B & C will use 0 also

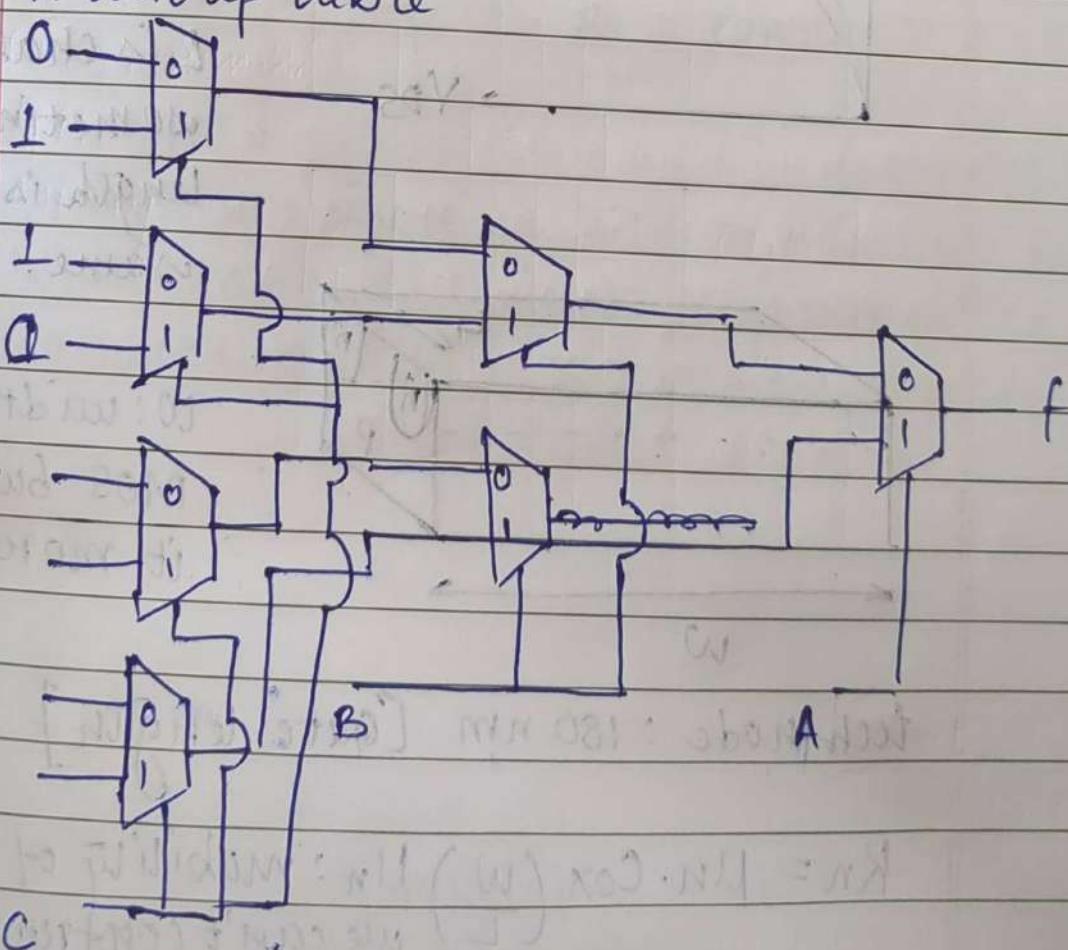
but C's o/p will be deselected]

Making adder using previous ckt

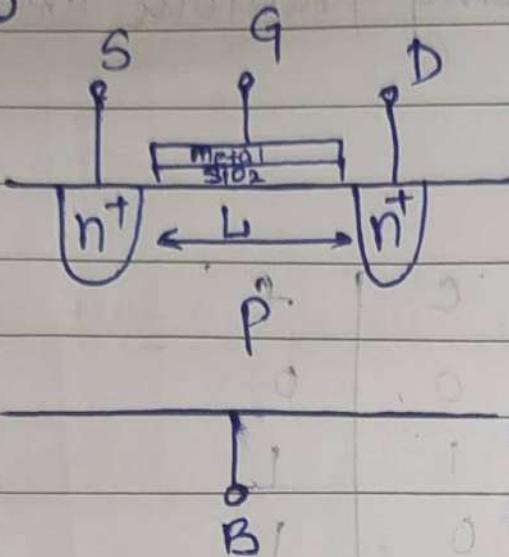
Truth Table

A	B	C	f
0	0	0	0
0	0	1	1
0	1	0	1
0	1	1	0
1	0	0	1
1	0	1	0
1	1	0	0
		1	1

look up table



★ MOS

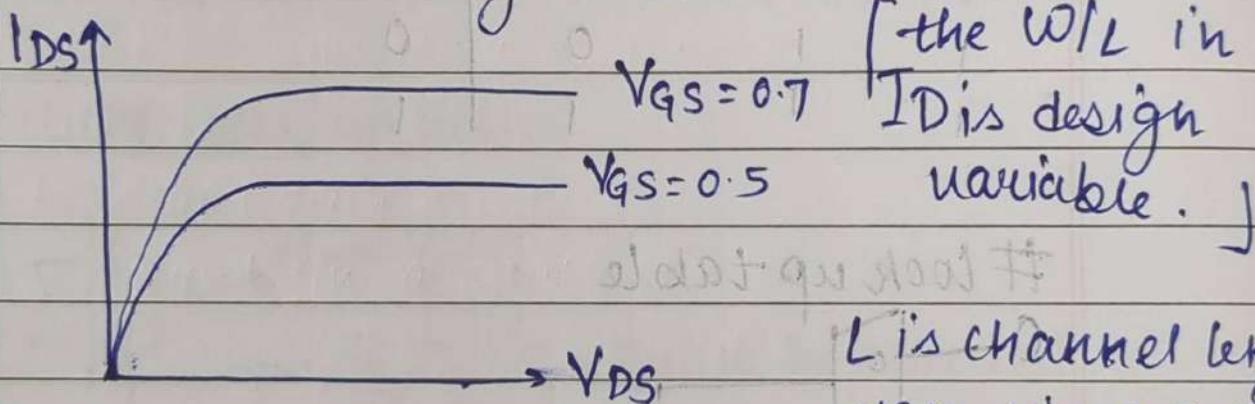


$$I_D = \frac{1}{2} K_n \left(\frac{W}{L} \right) (V_{GS} - V_t)^2$$

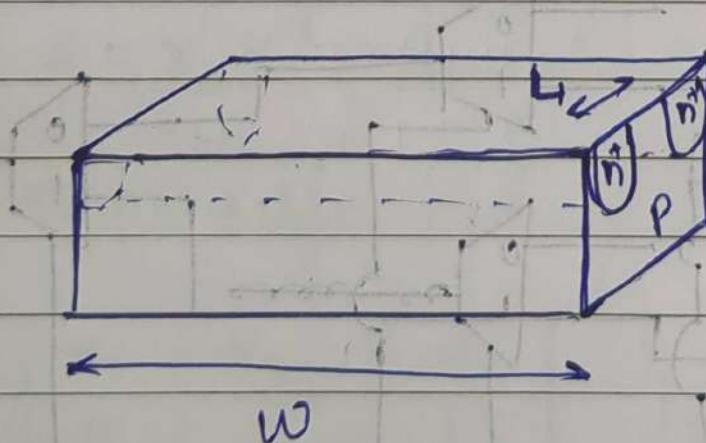
Nowadays, we use polysilicon at metal level instead of Aluminium.

→ Characteristics of MOS

- Threshold voltage (V_t)



L is channel length sometimes gate length is nearly same.



W : width of MOS but we want it more. i.e

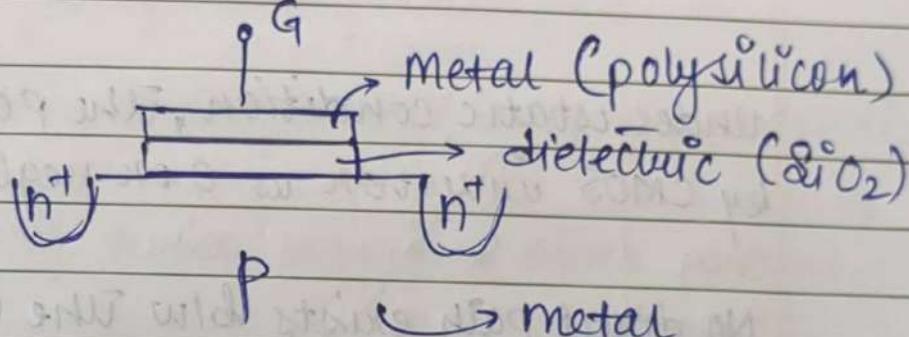
tech node : 180 nm [Gate length]

$$K_n = \mu_n \cdot C_{ox} \left(\frac{W}{L} \right)$$

μ_n : mobility of e^-
we can't control

$$C_{ox} : \text{oxide capacitance} = \frac{\epsilon_0}{\delta_{ox}}$$

The main problem with MOS is that it acts as a capacitor, and if we want fast switching ckt then value of $R \times C$ should be minimum. Any capacitor consists of two conductive plates filled with a dielectric.

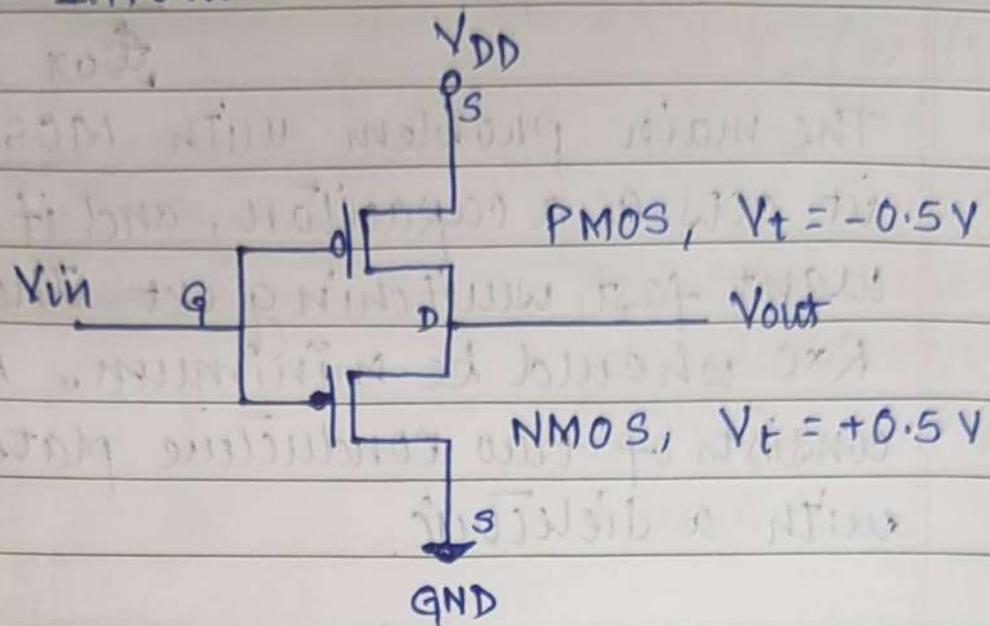


$$C = \frac{\epsilon_0 A}{d}, \text{ here } \epsilon_0 \text{ is a constt } \& A = w \times L$$

so we

deal with w/L
 If we increase w then w/L will be favourable but it will increase the capacitance which is not favourable.

★ CMOS Inverter

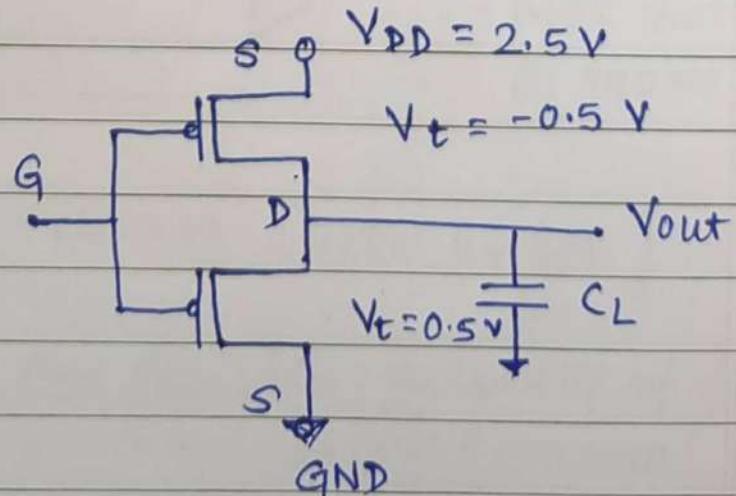


under static condition, the power drawn by CMOS inverter is 0 or negligible.

No direct path exists b/w the supply voltage & ground in a static condition.

When we have a NMOS, then the threshold is going to be some value as we need to create a channel. The V_{GS} is used to determine whether the NMOS is in on state or not.

i.e $V_{GSn} > V_t$ here V_t is threshold voltage



$$I_D = K_n \left(\frac{W}{L} \right) (V_{GS} - V_t) V_{DS} - \frac{1}{2} V_{DS}^2$$

classmate

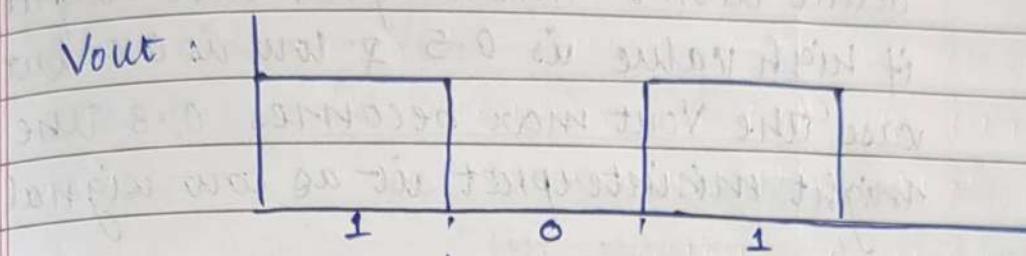
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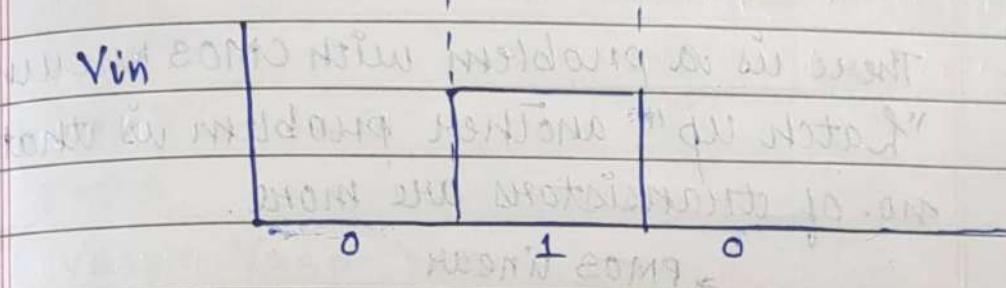
transfer characteristics

VTC: Voltage transmission curve

V_{out}



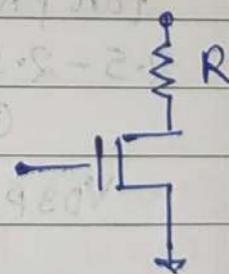
V_{in}



The above characteristic is of ideal condition we need to understand the VTC curve as to study noise margin & other parameters.

Fan-out: how many CMOS units can we connect with the V_{out} of previous. Ideally we can connect infinite no. of inverters but practically there is some leakage in.

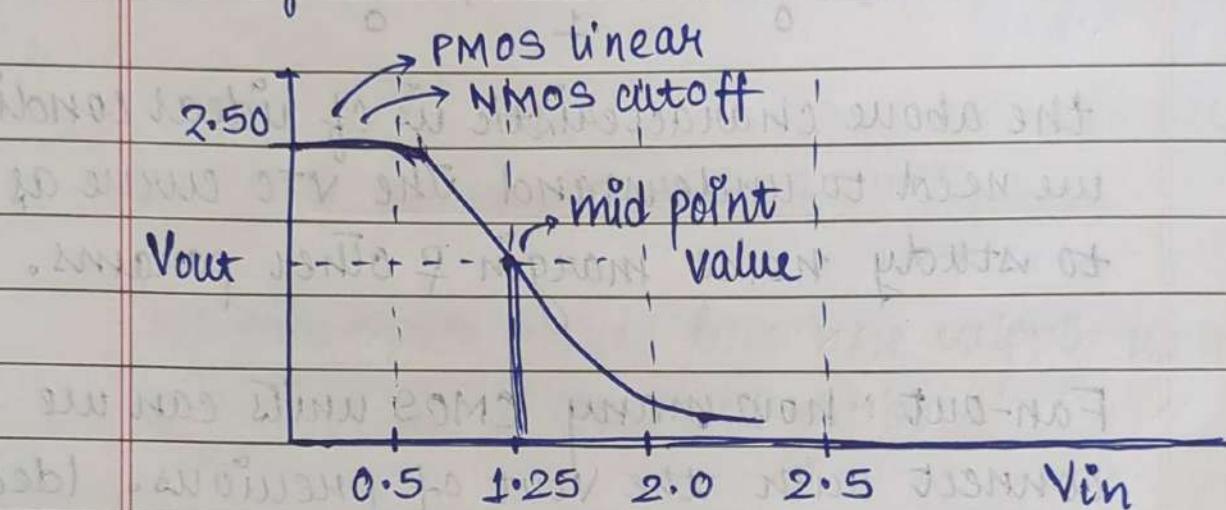
In comparison to the resistor of NMOS, the PMOS in CMOS offers less resistance.



Full swing is the parameter which determines the max achievable output voltage and min -11-.

we need more noise margin, so that the device won't misinterpret the output. ex: if high value is 0.5 & low is 0.0 but in case the V_{out} max becomes 0.3 the CMOS might misinterpret it as low signal.

NOTE : There is a problem with CMOS known as "latch up". another problem is that the no. of transistors are more.



$$V_{DS} = V_{GS} - V_t \quad \text{for } V_{in} = 0.5$$

for PMOS

$$2.5 - 2.5 = -2.0 - (-0.5)$$

$$0 = -1.5$$

$$V_{DSP} > -1.5 \quad \text{for PMOS}$$

$$V_{DSP} \geq V_{GSP} - V_t$$

it means PMOS is in linear region

PMOS is complementary to NMOS in all params
so saturation of PMOS is

$$V_{DSP} \leq V_{GSP} - V_{tp}$$

Now checking for NMOS at $V_{in} = 0.5 \text{ V}$

$$V_{DSN} = V_{GSN} - V_{tn}$$

$$2.5 - 0.0 = (0.5 - 0.0) - 0.5$$

$V_{DSN} \geq 0$ ie NMOS is operating in the saturation region.

for $V_{in} = 1.25$

PMOS

$$V_{DSP} = V_{GSP} - V_{tp}$$

$$1.25 - 2.5 = (1.25 - 2.5) - (-0.5)$$

$$-1.25 = (-1) + 0.5$$

$$-1.25 = -0.5$$

saturation

$V_{DSP} \geq -0.5$ ie PMOS is in linear

NMOS

$$1.25 - 0 = (1.25 - 0) - (0.5)$$

$$1.25 = 0.75$$

NMOS is in saturation

for $V_{in} = 2.0$

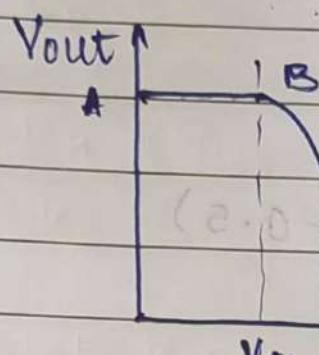
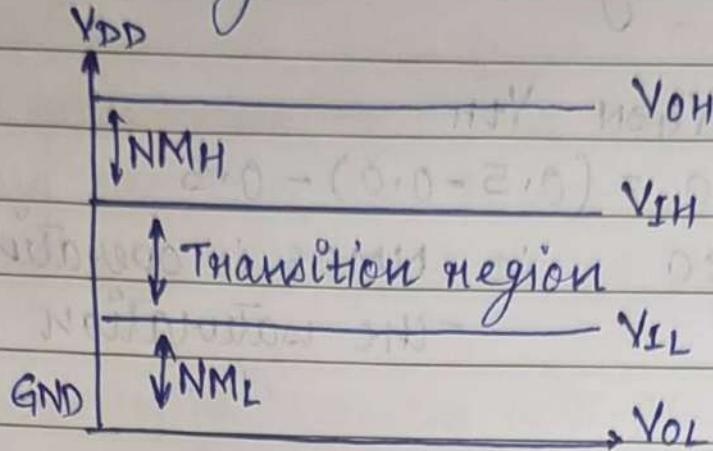
~~$$V_{DS} = V_{GS} - V_t$$~~

~~$$V_t =$$~~

PMOS = saturation

NMOS = linear

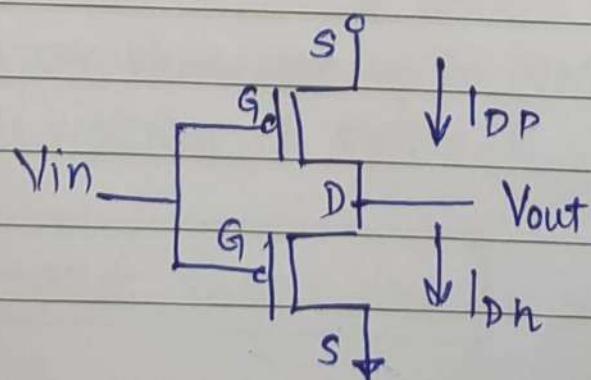
★ Noise margin



⇒ Noise margin is the range which is tolerable to the CMOS such that the output is not impacted. Here noise = Voltage in brief: it is total amount of acceptable v.

$$NML = V_{IL} - V_{OL}$$

V_{DD} is also written, but not equal to V_{OH} because there might be some voltage drop across PMOS.



Let the NMOS be operating in saturation region & PMOS in linear region

$$I_{dn} = \frac{1}{2} K_n (V_{GSn} - V_{tn})^2$$

(saturation)
NMOS

$$I_{dp} = K_p \left[(V_{GSp} - V_{to}) \cdot V_{DSP} - \frac{1}{2} V_{DSP}^2 \right]$$

equating both of them

$$I_{dn} = I_{dp}$$

$$\frac{1}{2} K_n [V_{in} - V_{tn}]^2 = K_p [(V_{in} - V_{DD} - V_{tp})(V_{out} - V_{DD}) - \frac{1}{2} (V_{out} - V_{DD})^2]$$

"Considering for B"

Now we are interested in finding V_{IL} .
diff w.r.t V_{in}

~~$$\frac{1}{2} K_n (V_{in} - V_{tn})^2 = K_p [$$~~

$$K_n (V_{in} - V_{tn}) = K_p \times \left[\frac{dV_{in}}{dV_{in}} \cdot (V_{out} - V_{DD}) + \left(\frac{dV_{out}}{dV_{in}} - 0 \right) \cdot (V_{in} - V_{DD} - V_{to}) - \frac{1}{2} \times 2 (V_{out} - V_{DD}) \cdot \frac{dV_{out}}{dV_{in}} \right]$$

$$K_n(V_{in} - V_{th}) = k_p \left[(V_{out} - V_{DD}) + \frac{dV_{out}}{dV_{in}} (V_{in} - V_{DD}) \right. \\ \left. - (V_{out} - V_{DD}) \frac{dV_{out}}{dV_{in}} \right]$$

assuming that $dV_{out}/dV_{in} = -1$ (slope)

$$\frac{K_n}{k_p} (V_{in} - V_{th}) = \left[V_{out} - V_{DD} - V_{in} + V_{DD} + V_{tp} \right. \\ \left. + V_{out} - V_{DD} \right]$$

$$\frac{K_n}{k_p} (V_{in} - V_{th}) = \left[2V_{out} - V_{DD} + V_{tp} - V_{in} \right]$$

let $K_n/k_p = K_H$ for simplification

$$K_H V_{in} + V_{in} = 2V_{out} - V_{DD} + V_{tp} + K_H V_{th}$$

$$V_{in} = \left[\frac{2V_{out} - V_{DD} + V_{tp} + K_H V_{th}}{1 + K_H} \right]$$

as we are calculating from point B.
i.e. V_{IL} , $V_{in} = V_{IL}$ also

$$V_{IL} = \frac{2V_{out} - V_{DD} + V_{tp} + K_H V_{th}}{1 + K_H}$$

$K_H = k_p/K_n$, it is in our hands
because rest of the params are not
controllable.

($V_{DD} = 1.8$ for 180nm MOS ckt)
 we can't actually control V_{DD} , like there isn't much freedom because it is min required.

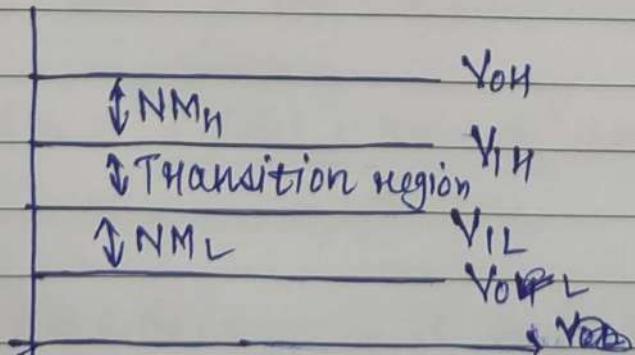
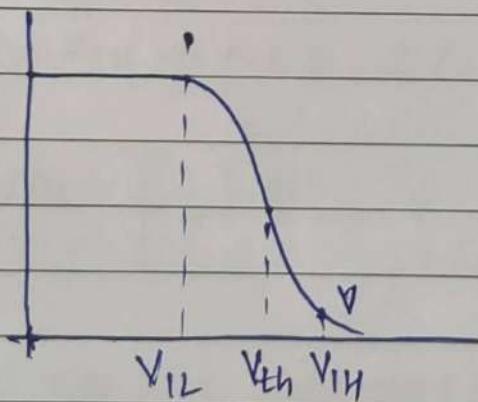
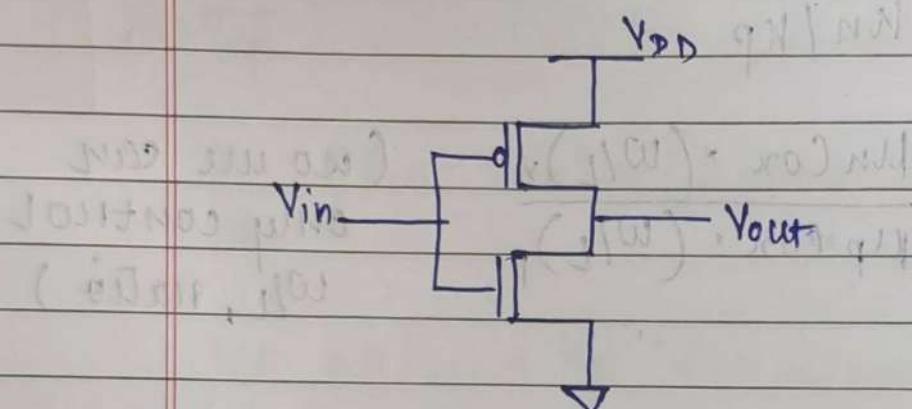
$$K_n = \mu_n C_{ox} \left(\frac{W}{L} \right)_n \quad \left[C_{ox} = \frac{\epsilon_{ox}}{t_{ox}} \right]$$

$$K_H = K_n / K_p$$

$$K_H = \frac{\mu_n C_{ox} \cdot (W/L)_n}{\mu_p C_{ox} \cdot (W/L)_p} \quad (\text{so we can only control } W/L \text{ ratio})$$

$$V_{IH} = \frac{V_{DD} + V_{TO,p} + K_H (2V_{out} + V_{to,h})}{1 + K_H}$$

$$V_{th} = V_{to,n} + \frac{\frac{1}{K_H} (V_{DD} + V_{to,p})}{1 + \frac{1}{K_H}}$$



V_{IH} is the minimum input voltage, which can be interpreted as a logic 1.

V_{IL} is the maximum input voltage, which can be interpreted as a logic 0.

Ideally V_{OH} should be equal to the supply voltage V_{DD} . & V_{OL} should be 0 if there is no drop.

$$NM_H = V_{OH} - V_{IH} \quad // \text{high noise margin}$$

$$NM_L = V_{OL} - V_{IL} \quad // \text{low noise margin}$$

If not mentioned then $V_{OH} \approx V_{DD}$

$$\& V_{OL} \approx GND$$

• Definition of (I) in input output switching

$$0.5V(2.8) + 0.2V \rightarrow 0.7V - 0.1V = 0.6V$$

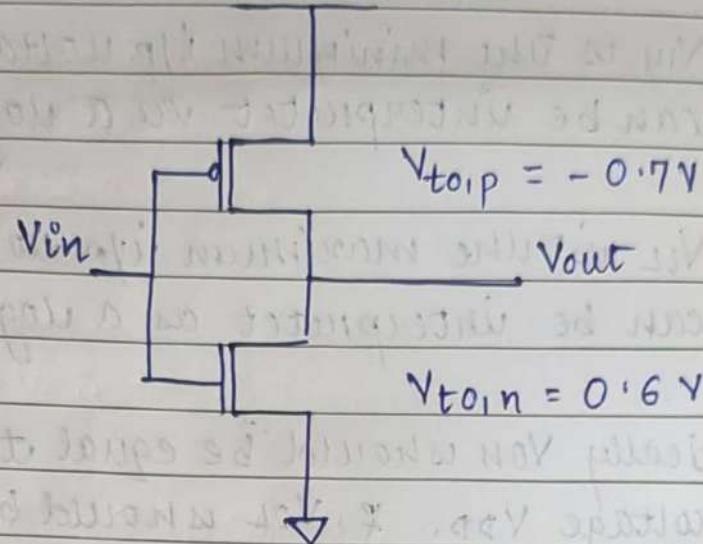
$$2.8 + 1$$

$$2.1 + 0.4 \rightarrow 2.5V =$$

TBR: Kn/Kp ratio is almost 2.5 nearly in all cases.

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$$V_{DD} = 3.3 \text{ V}$$



$$K_n = 200 \mu\text{A}/\text{V}^2$$

$$K_p = 80 \mu\text{A}/\text{V}^2$$

$$V_{IL} = \frac{2V_{out} + V_{to,p} - V_{DD} + K_R V_{th}}{1 + K_R} \quad \textcircled{1}$$

$$V_{IH} = \frac{V_{DD} + V_{to,p} + K_R (2V_{out} + V_{to,n})}{1 + K_R} \quad \textcircled{2}$$

$$V_{th} = V_{to,n} + \frac{\frac{1}{K_R} (V_{DD} + V_{to,p})}{1 + \frac{1}{K_R}} \quad \textcircled{3}$$

$$K_R = \frac{K_n}{K_p} = 2.5$$

Putting given data in $\textcircled{1}$ st formula.

$$V_{IL} = \frac{2V_{out} - 0.7 - 3.3 + (2.5) \times 0.6}{1 + 2.5}$$

$$= \frac{2V_{out} - 4.0 + 1.5}{3.5}$$

$$V_{IL} = \frac{2V_{out} - 2.5}{3.5} \Rightarrow V_{IL} = 0.57V_{out} - 0.71$$

We know that, for I_L , the PMOS is in linear region & NMOS is in saturation region, also $V_{IL} = V_{in}$, so.

$$\frac{1}{2}k_n(V_{in} - V_{tn})^2 = k_p [(V_{in} - V_{DD} - V_{tp})(V_{out} - V_{DD})] - \frac{1}{2}(V_{out} - V_{DD})^2$$

$$\textcircled{2} \quad \frac{k_n}{k_p} (V_{in} - V_{tn})^2 = k_p [(V_{in} - V_{DD} - V_{tp})(V_{out} - V_{DD})] - (V_{out} - V_{DD})$$

$$2.5(V_{IL} + 0.6)^2 = 2 \times (V_{IL} - 3.3 - (-0.7)) \times (V_{out} - 3.3) \quad \text{--- } \textcircled{4}$$

Putting V_{IL} in Eqn \textcircled{4}

$$\Rightarrow 2.5(0.57V_{out} - 0.71 - 0.6)^2$$

$$= [2(0.57V_{out} - 0.71 - 3.3 + 0.70)(V_{out} - 3.3)]$$

$$- [V_{out} - 3.3]$$

$$\Rightarrow 2.5(0.57V_{out} - 1.31)^2$$

$$= [2(0.57V_{out} - 3.4)(V_{out} - 3.3)] - [V_{out} - 3.3]$$

$$\Rightarrow 0.812V_{out}^2 + 4.290 - 3.73V_{out}$$

$$= (1.14V_{out} - 6.8)(V_{out} - 3.3) - V_{out} - 10.89 + 6.6V_{out}$$

$$\Rightarrow 0.812 V_{out}^2 - 3.73 V_{out} + 4.290 \\ = 1.414 V_{out}^2 - 3.76 V_{out} - 6.8 V_{out} + 22.4 \\ - V_{out}^2 + 6.6 V_{out} - 10.89$$

$$\Rightarrow 0.812 V_{out}^2 - 3.73 V_{out} + 4.290 \\ = 0.414 V_{out}^2 + 2.87 V_{out} - 6.8 V_{out} - 11.51$$

$$\Rightarrow 0.812 x^2 - 3.73 x + 4.29 \\ = 0.414 x^2 - 3.93 x - 11.51$$

$$\Rightarrow 0.67 V_{out}^2 + 0.05 V_{out} - 7.22 = 0$$

$$V_{out}^2 + 0.074 V_{out} - 10.77$$

$$V_{out} = \left(\frac{-0.074 \pm \sqrt{(0.074)^2 + 4(10.77)}}{2(10.77)} \right)$$

$$= - \left[\frac{-0.074 \pm \sqrt{5.476 + 43.08}}{21.54} \right]$$

$$V_{out} = -3.21 \text{ or } 3.14$$

X
not acceptable

$$V_{out} = 3.14$$

$$V_{IL} = 0.57 V_{out} - 0.71$$

$$\boxed{V_{IL} = 1.07}$$

$$V_{IH} = \frac{V_{DD} + V_{TO1P} + KR(2V_{out} + V_{TO1N})}{1+KR}$$

for V_{IH} , NMOS will be in linear &
PMOS will be in saturation.

$$\begin{aligned} V_{IH} &= 3.3 + (-0.7) + 2.5(2V_{out} + 0.6) \\ &= \frac{3.3 - 0.7 + 5V_{out} + 1.5}{3.5} \end{aligned}$$

$$V_{IH} = 1.43V_{out} + 1.17$$

Writing drain current equation for both

$$I_{Dp} = \frac{1}{2} K_p (V_{GSp} - V_{tp})^2$$

$$I_{Dn} = K_n [(V_{GSn} - V_{ton})(V_{DSn}) - \frac{1}{2}(V_{DSn})^2]$$

after solving for V_{IH} , we get $V_{out} = 0.6$

$$V_{IH} = 2.028$$

$$I = I_0 (e^{V/nV_T} - 1)$$

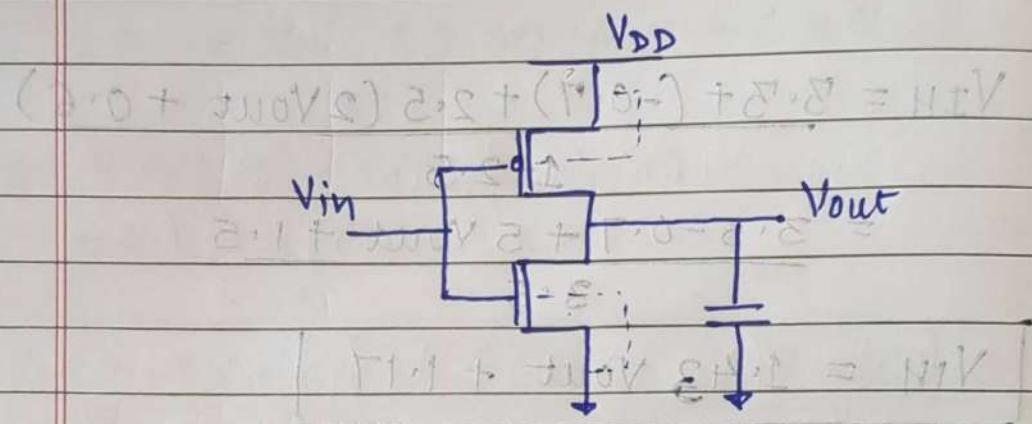
V_T = Thermal Voltage

classmate

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- ① Power dissipation across CMOS inverter
 - ↳ Static power dissipation (P_{dc}) leakage current
 - ↳ Dynamic power dissipation (P_{dyn})
 - ↳ Short circuit power loss (P_{sc})



$$P_{diss} = P_{dc} + P_{dyn} + P_{sc}$$

\Rightarrow We can static power dissipation due to leakage current. $I = I_0 (e^{V/nV_T} - 1)$

It is completely unwanted but it is never 0. In terms of eqⁿ, we can write static power as

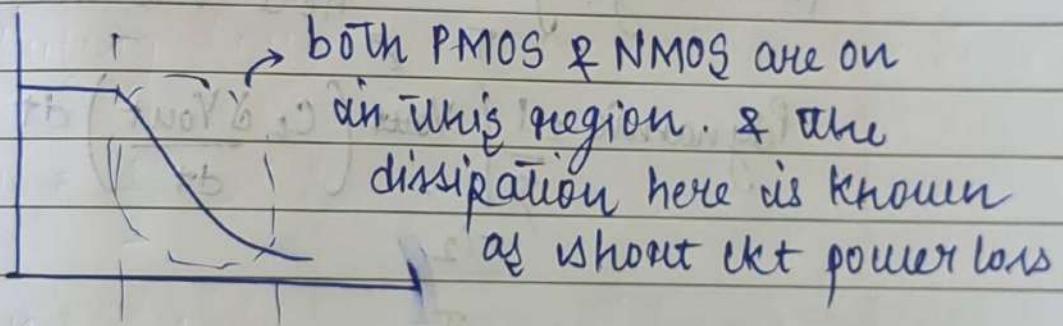
$$P_{dc} = I_0 (e^{V/nV_T} - 1) \times V_{DD}$$

P_{dc} is really really really low. but in VLSI design, there are hell lot of transistors (around a million), so the value of P_{dc} becomes considerable now.

→ dynamic power dissipation

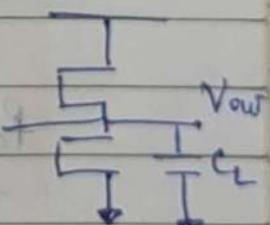
when the I/O goes from $0 \rightarrow 1$, the PMOS gets off & NMOS acts as a discharging path. & the power is dissipated through it. The dynamic power dissipation is there, due to charging & discharging of capacitor. or it can be more precise

[Dynamic is due to switching activity]



Short ckt power dissipation loss is for really less time and at that time both NMOS & PMOS are in ON state & the current gets a direct path to ground.

$$P_{dynamic} = \frac{1}{T} \int_0^T V(t) \cdot i(t) dt$$

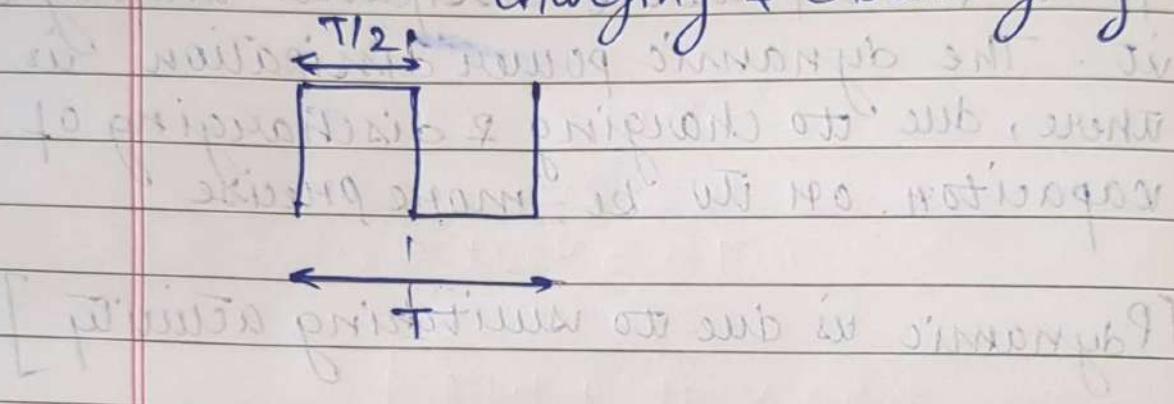


$$P_{dynamic} = \frac{1}{T} \int_0^T V_{out} \times C \times \frac{dV}{dt} dt$$

$$P_{dynamic} = \frac{1}{T} \int_{0}^{T/2} V_{out} \times \left(-C_L \times \frac{dV_{out}}{dt} \right) dt$$

when charging is done then
else -

discharging why $T/2$ because half T will be
charging & discharging



for charging

here V is across PMOS
no V

$$P_{dynamic} = \frac{1}{T} \int_{T/2}^T V_{out} \left(C_L \frac{dV_{out}}{dt} \right) dt = V_{DD} - V_{out}$$

$$P_{dynamic} = \frac{1}{T} \int_{T/2}^T (V_{DD} - V_{out}) \left(C_L \frac{dV_{out}}{dt} \right) dt$$

Now adding both

$$P_{dyn} = \frac{1}{T} \times C_L \left[- \int_0^{T/2} V_{out} \frac{dV_{out}}{dt} + \int_{T/2}^T (V_{DD} - V_{out}) \frac{dV_{out}}{dt} \right]$$

$$\begin{aligned}
 P_{\text{dym}} &= \frac{1}{T} \cdot C_L \left[\left[-\frac{V_{\text{out}}^2}{2} \right]_0^{T/2} + \left[\frac{\sqrt{V_{\text{dd}} \cdot V_{\text{out}} - V_{\text{out}}^2}}{2} \right]_{-T/2}^T \right] \\
 &= \frac{1}{T} C_L \left[\left[-\frac{V_{\text{out}}^2}{2} \right]_{0=V_{\text{dd}}}^{T/2=0} + V_{\text{dd}} \left[V_{\text{out}} \right]_{-T/2}^T - \left[\frac{V_{\text{out}}^2}{2} \right]_{-T/2}^T \right] \\
 &= \frac{1}{T} \times C_L \left[-\left[-\frac{V_{\text{dd}}^2}{2} \right] + V_{\text{dd}} \times [V_{\text{dd}} - 0] - \left[\frac{V_{\text{dd}}^2 - 0}{2} \right] \right] \\
 &= \frac{1}{T} \times C_L \left[\frac{V_{\text{dd}}^2 + V_{\text{dd}}^2 - V_{\text{dd}}^2}{2} \right] \\
 &= \frac{1}{T} \times C_L \times V_{\text{dd}}^2
 \end{aligned}$$

$$P_{\text{dynamic}} = \frac{1}{T} \cdot C_L \cdot V_{\text{dd}}^2$$

here T is time period,
so $f = 1/T$ here

$$[P_{\text{dynamic}} = f \cdot C_L \cdot V_{\text{dd}}^2]$$

Now, we can see that, it is still ~~not~~ dependent on the switching activity.

f can be depicted as α_{0-1}